
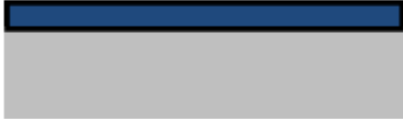




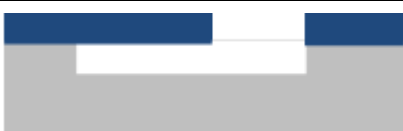


Cantilever Fabrication

Date	Bay	Process	Device cross section
	Wet etch	RCA Cleaning	
	Diffusion	LPCVD silicon Nitride Deposition	
	Inline characterisation	Inspection: thickness measurement	
	Lithography	Optical lithography (Pattern definition)	
	Dry etch	Silicon Nitride etch	
	Dry etch	Release etch	
	Dry etch	Photoresist Removal	



Silicon



Photoresist



Silicon nitride